## **IN THE CLAIMS**

Please amend claims 28 and 31 as follows:

28. (Amended) A gaseous composition comprising at least one precursor of a metal oxide, [and] an accelerant selected from the group consisting of organic phosphites, organic borates, and water, and a precursor of silicon oxide having the formula R<sub>m</sub>O<sub>n</sub>Si<sub>p</sub>, where m is from 3 to 8, n is from 1 to 4, p is from 1 to 4, and R is independently chosen from hydrogen and acyl, straight, cyclic, or branched-chain alkyl and substituted alkyl or alkenyl of from one to about six carbons, and phenyl or substituted phenyl, and wherein said composition is gaseous at a temperature below about 200°C at atmospheric pressure and is adapted to deposit at least a first layer of an oxide and silicon oxide onto a glass at a rate of deposition greater than 350Å/sec.

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31. (Amended) A gaseous composition comprising a metal oxide precursor, [and] an accelerant selected from the group consisting of phosphites, borates, water, alkyl phosphine, arsine and borane derivatives, PH<sub>3</sub>, AsH<sub>3</sub>, B<sub>2</sub>H<sub>6</sub>, O<sub>2</sub>, N<sub>2</sub>O, NF<sub>3</sub>, NO<sub>2</sub>, and CO<sub>2</sub>, and a precursor of silicon oxide having the formula R<sub>m</sub>O<sub>n</sub>Si<sub>p</sub>, where m is from 3 to 8, n is from 1 to 4, p is from 1 to 4, and R is independently chosen from hydrogen and acyl, straight, cyclic, or branched-chain alkyl and substituted alkyl or alkenyl of from one to about six carbons, and phenyl or substituted phenyl, and wherein said composition is gaseous at a temperature below about 200°C at atmospheric pressure and is adapted to deposit at least a first layer of an oxide and silicon oxide onto a glass at a rate of deposition greater than 350Å/sec.

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